Metrology system for analyzing panel misregistration in a panel manufacturing process and providing appropriate information for adjusting panel manufacturing processes.

A metrology system to analyse panel misregistration in a panel manufacturing process includes a software controlled system which checks defined panel parameters on the four corners of a panel and related artwork for processing with a master pattern etched on a glass reference with a machine vision measuring system. The panel or artwork being checked is positioned by panel center registration means to align the center of the panel with the center of the master pattern. Displacement and rotational differences are entered under software control into a data base and analyzed by a stored program intelligent analyses system into a plurality of parameters based on a parameter model which permits an analysis of the cause of the misregistration.
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<th>Category</th>
<th>Citation of document with indication, where appropriate, of relevant passages</th>
<th>Relevant to claim</th>
<th>CLASSIFICATION OF THE APPLICATION (Int. Cl.5)</th>
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The present search report has been drawn up for all claims

Place of search: THE HAGUE  
Date of completion of the search: 14 JULY 1992  
Examiner: BERTIN M., N., J.

**CATEGORY OF CITED DOCUMENTS**

X: particularly relevant if taken alone
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